

**METHOD AND APPARATUS FOR PROPER ORDERING
OF REGISTRATION DATA**

ABSTRACT

5 A photomask or reticle including a unique set of alignment attributes at separate and
distinguishable field points is put in the reticle plane of a photolithographic projection
system. The reticle pattern is exposed onto a resist coated wafer or substrate and processed
through the final few steps of the photolithographic process. The resulting array of
alignment attributes are then measured using a standard optical overlay metrology tool. The
10 overlay tool is driven by a set of software instructions. By comparing the resulting overlay
data to the placement error encoded on the reticle it can be determined if the data has been read
or displayed in the correct order.

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